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Characterization of the cleaning process on a transferred graphene

Li-Wei Huang, Cheng-Kai Chang, Fan-Ching Chien, Kuei-Hsien Chen, Peilin Chen, Rong Chen and Chia-Seng Chang

J. Vac. Sci. Technol. A **32**, 050601 (2014); <http://dx.doi.org/10.1116/1.4886735>

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Surface temperature: A key parameter to control the propanethiol plasma polymer chemistry

Damien Thiry, Francisco J. Aparicio, Priya Laha, Herman Terryn and Rony Snyders

J. Vac. Sci. Technol. A **32**, 050602 (2014); <http://dx.doi.org/10.1116/1.4890672>

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Sample-morphology effects on x-ray photoelectron peak intensities. II. Estimation of detection limits for thin-film materials

Cedric J. Powell, Wolfgang S. M. Werner and Werner Smekal

J. Vac. Sci. Technol. A **32**, 050603 (2014); <http://dx.doi.org/10.1116/1.4891628>

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Photoluminescence behavior of plasma synthesized Si nanocrystals oxidized at different temperatures in pure O₂ and H₂O

Stephen L. Weeks, Rohan P. Chaukulkar, Paul Stradins and Sumit Agarwal

J. Vac. Sci. Technol. A **32**, 050604 (2014); <http://dx.doi.org/10.1116/1.4892387>

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Toroidal plasma enhanced CVD of diamond films

John Zvanya, William Holber, Christopher Cullen, Thomas Morris, Andrew Basnett, F. Basnett, Jeffrey Hettinger and Robert R. Krchnavek

J. Vac. Sci. Technol. A **32**, 050605 (2014); <http://dx.doi.org/10.1116/1.4893416>

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Effect of interfacial interactions on the thermal conductivity and interfacial thermal conductance in tungsten-graphene layered structure

K. Jagannadham

J. Vac. Sci. Technol. A **32**, 051101 (2014); <http://dx.doi.org/10.1116/1.4890576>

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Haseeb Kazi, Jessica Rimsza, Jincheng Du and Jeffry Kelber

J. Vac. Sci. Technol. A **32**, 051301 (2014); <http://dx.doi.org/10.1116/1.4890119>[+ VIEW DESCRIPTION](#)**Correction of aspect ratio dependent etch disparities**

Robert L. Bates, Matthew J. Goeckner and Lawrence. J. Overzet

J. Vac. Sci. Technol. A **32**, 051302 (2014); <http://dx.doi.org/10.1116/1.4890004>[+ VIEW DESCRIPTION](#)**Smoothing single-crystalline SiC surfaces by reactive ion etching using pure NF₃/Ar mixture gas plasmas**

Akimasa Tasaka, Yuki Kotaka, Atsushi Oda, Morihiro Saito, Tetsuro Tojo and Minoru

J. Vac. Sci. Technol. A **32**, 051303 (2014); <http://dx.doi.org/10.1116/1.4893421>[+ VIEW DESCRIPTION](#)

SURFACES**Surface oxidation of GaN(0001): Nitrogen plasma-assisted cleaning for ultrahigh vacuum applications**

Subhashis Gangopadhyay, Thomas Schmidt, Carsten Kruse, Stephan Figge, Detlef Hommel and Jens Falta

J. Vac. Sci. Technol. A **32**, 051401 (2014); <http://dx.doi.org/10.1116/1.4886956>[+ VIEW DESCRIPTION](#)**Desorption and sublimation kinetics for fluorinated aluminum nitride surfaces**

Sean W. King, Robert F. Davis and Robert J. Nemanich

J. Vac. Sci. Technol. A **32**, 051402 (2014); <http://dx.doi.org/10.1116/1.4891650>[+ VIEW DESCRIPTION](#)**Evaluating tantalum oxide stoichiometry and oxidation states for optimal memris performance**

Michael T. Brumbach, Patrick R. Mickel, Andrew J. Lohn, Alex J. Mirabal, Michael A. Kalan, James E. Stevens and Matthew J. Marinella

J. Vac. Sci. Technol. A **32**, 051403 (2014); <http://dx.doi.org/10.1116/1.4893929>[+ VIEW DESCRIPTION](#)

THIN FILMS**Fabrication of Sr silicate buffer layer on Si(100) substrate by pulsed laser deposit using a SrO target**

Atsuhiko Imanaka, Tsubasa Sasaki, Yasushi Hotta and Shin-ichi Satoh

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Suwa and Tadahiro Ohmi

J. Vac. Sci. Technol. A **32**, 051502 (2014); <http://dx.doi.org/10.1116/1.4886770>

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Jing Yang, Degang Zhao, Desheng Jiang, Ping Chen, Jianjun Zhu, Zongshun
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Effect of AC target power on AlN film quality

Katherine Knisely and Karl Grosh

J. Vac. Sci. Technol. A **32**, 051504 (2014); <http://dx.doi.org/10.1116/1.4886776>

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**ZnO nanorod growth by plasma-enhanced vapor phase transport with different g
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Chang-Yong Kim, Hee-bong Oh, Hyukhyun Ryu, Jondo Yun and Won-Jae Lee

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**Effect of nitrogen upon structural and magnetic properties of FePt in FePt/AlN mu
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Tenghua Gao, Cong Zhang, Takumi Sannomiya, Shinji Muraishi, Yoshio Nakamura
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Ag-Pd-Cu alloy inserted transparent indium tin oxide electrodes for organic solar

Hyo-Joong Kim, Ki-Won Seo, Han-Ki Kim, Yong-Jin Noh and Seok-In Na

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**Detection of charge carrier confinement into mobile ionic defects in nanoporous
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Juan Borja, Joel L. Plawsky, Toh-Ming Lu, William N. Gill, Thomas M. Shaw, Robert I
Laibowitz, Eric G. Liniger, Stephan A. Cohen, Robert Rosenberg and Griselda Bonill

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